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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant : Hsiu-Chun LEE et al. Confirmation No: 3353  
Appl. No. : 10/751,503  
Filed : January 6, 2004  
Title : METHOD FOR FORMING SHALLOW TRENCH IN  
SEMICONDUCTOR DEVICE

TC/A.U. : 2823  
Examiner : H. M. Lee

Docket No.: : LEEH3016/REF  
Customer No: : 23364

**PETITION FOR EXTENSION OF TIME**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Applicants request that the period for response to the outstanding official action in this case be extended pursuant to 37 CFR 1.136 (a) for ONE (1) month to May 19, 2005.

The fee set in 37 CFR 1.17(a)(1) for a one month extension of time is \$120.00 and a check in this amount is submitted herewith. Please charge any additional fee required for this extension to Deposit Account No. 02-0200. A duplicate copy of this paper is attached.

Respectfully submitted,

BACON & THOMAS, PLLC

05/13/2005 HALI11 00000084 10751503  
01 FC:1251 120.00 OP

By: Richard E. Fichter  
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REF:kdd  
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May 12, 2005